IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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) Group Art Unit: Unassigned
) Examiner: Unassigned)

For: METHOD OF FORMING POLYSILICON THIN FILM TRANSISTOR

Commissioner for Patents

MAIL STOP PATENT APPLICATION

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicant brings to the attention of the Examiner the documents listed on the attached PTO-1449. This Information Disclosure Statement is being filed within three months of the filing date of the above-referenced application.

A copy of the listed document is attached.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that the listed document is material or constitutes "prior art." If it should be determined that the listed document does not constitute "prior art" under United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such document. Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed document, should the document be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 50-0310.

Respectfully submitted,

MORGAN, LEWIS & BOCKIUS LLP

Robert J. Goodell, Reg. No. 41,040

Date: October 30, 2003

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Attorney Docket No. Serial No. 053785-5158 Unassigned INFORMATION DISCLOSURE CITATION Applicants (Use several sheets if necessary) Seok-Woo LEE Filing Date **PTO Form 1449** Group October 30, 2003 Unassigned **U.S. PATENT DOCUMENTS** *Examiner Document Sub Initial Number Date Name Class Class Filing Date **FOREIGN PATENT DOCUMENTS** Document Sub **Translation** Number Class Class Date Country YES NO OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) S. MATSUDA, et al. "Novel Corner Rounding Process For Shallow Trench Isolation Utilizing MSTS (Micro-Structure Transformation of Silicon)." IEDM Technical Digest. pp. 137-140, 1998. Examiner Date Considered Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through

citation if not in conformance and not considered. Include copy of this form with next communication to

applicant.